

EUROPEAN PATENT OFFICE

Patent Abstracts of Japan

PUBLICATION NUMBER : 10142628
 PUBLICATION DATE : 29-05-98

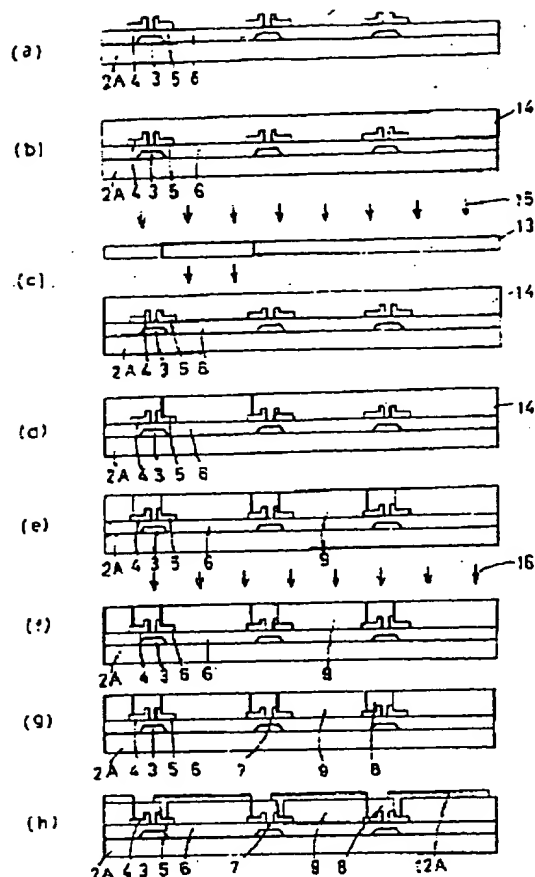
APPLICATION DATE : 07-11-96
 APPLICATION NUMBER : 08294807

APPLICANT : MATSUSHITA ELECTRIC IND CO LTD;

INVENTOR : ONISHI HIROYUKI;

INT.CL. : G02F 1/136 G02B 5/20 G02F 1/1335

TITLE : ACTIVE MATRIX SUBSTRATE AND
 MANUFACTURE THEREOF



ABSTRACT : PROBLEM TO BE SOLVED: To provide an active matrix substrate, which is provided with a high yield, high brightness, and a high contrast, and a manufacturing method thereof.

SOLUTION: After a nonlinear element constructed of a thin film transistor is formed, an organic polymer insulating film 14 made of organic polysilane and the like is applied once, and then, a contact hole reaching a drain electrode in the thin film transistor is bored in the organic polymer insulating film 14, and subsequently, a part of the organic polymer insulating film 14 is colored in three colors R, G, B while the rest part is colored in black, and consequently, a color filter 9 and a black matrix 8 are formed in the organic polymer insulating film 14. An ITO pixel electrode 12A is formed on the color filter 9 so as to be connected to the drain electrode in the thin film transistor through the contact hole.

COPYRIGHT: (C) JPO